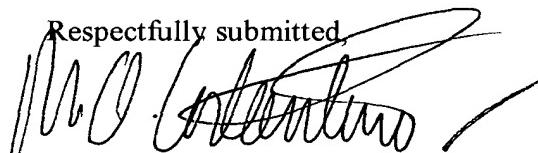


REMARKS

Claims 1-90 are pending. By this Amendment, claims 47-90 are added, and claims 16, 19, 22, 33 and 34 are amended. The attached Appendix includes marked-up copies of each rewritten claim (37 C.F.R. §1.121(c)(1)(ii)).

The November 19, 2002 RCE requested that prosecution be suspended. Upon entry of this Amendment and the Information Disclosure Statement filed herewith, Applicant requests that prosecution be resumed. Applicant requests the Examiner to consider the references submitted in the attached Information Disclosure Statement, along with the references submitted with the Information Disclosure Statement that was filed with the RCE on November 19, 2002.

Examination and allowance in due course are earnestly solicited.

Respectfully submitted,  
  
Mario A. Costantino  
Registration No. 33,565

MAC/nra

Attachments:

Appendix  
Amendment Transmittal  
Information Disclosure Statement

Date: December 16, 2002

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<b>DEPOSIT ACCOUNT USE AUTHORIZATION</b> Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461
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## APPENDIX

## Changes to Claims:

Claims 47-90 are added.

The following is a marked-up version of the amended claims:

16. (Amended) The exposure apparatus of claim 1, wherein the illumination optical system comprises:

a light radiation source that outputs the lighta radiation beam;

a reflective optical integrator that makes uniform an illumination distribution of light radiation from the light radiation beam; and

a light-radiation guiding optical system arranged in an optical path between the light-radiation source and the reflective optical integrator, and that guides the light-radiation beam from the light-radiation source to the reflective optical integrator.

19. (Amended) An exposure apparatus comprising:

an illumination optical system having a plurality of reflective components that guide a light radiation beam to a mask;

a projection system that projects a pattern of the mask onto a photosensitive substrate;

a drive that relatively moves the photosensitive substrate and the mask with respect to the projection system along a specified scanning exposure direction;

a first telecentricity adjustment mechanism that applies an oblique component to telecentricity in one of: (a) an exposure field of the projection system, and (b) an illumination field formed on the mask; and

a second telecentricity adjustment mechanism that adjusts telecentricity changing in accordance with a position from an optical axis in one of: (a) the exposure field of the projection system, and (b) the illumination field formed on the mask;

wherein the first and second telecentricity adjustment mechanisms respectively adjust at least some of the plurality of reflective components of the illumination optical system.

22. (Amended) The exposure apparatus of claim 19, wherein the illumination optical system comprises:

a light radiation source that outputs the light radiation beam;  
a reflective integrator that makes uniform an illumination distribution of light radiation from the light radiation beam on the photosensitive substrate or the mask; and  
a light radiation guiding optical system arranged between the light radiation source and the reflective integrator that guides the light radiation beam from the light radiation source to the reflective integrator.

33. (Amended) The method of claim 32, wherein the oblique component to telecentricity is applied by adjusting an illumination optical component that is different from the at least one common different illumination optical componentcomponents, and the telecentricity changing in accordance with a position from the optical axis is adjusted by adjusting an illumination optical component that is different from the illumination optical component adjusted to apply the oblique component to telecentricity.

34. (Amended) The method of claim 32, wherein the oblique component to telecentricity is applied by adjusting an illumination optical component that is different from the at least one common different illumination optical componentcomponents, and the telecentricity changing in accordance with a position from the optical axis is adjusted by adjusting an illumination optical component that is the same as the illumination optical component adjusted to apply the oblique component to telecentricity.